

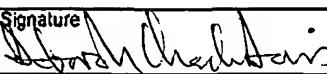
Sheet 1 of 1

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-882001	Application No. 10/693,373
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))		Applicant Yan Borodovsky	
		Filing Date October 24, 2003	Group Art Unit 1756

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
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Foreign Patent Documents or Published Foreign Patent Applications							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation Yes      No
	AL						
	AM						
	AN						
	AO						
	AP						

Other Documents (Include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
YD	AQ	"Gratings of regular arrays and ultraminiature exposures for ultralarge scale integrated circuit phase-shift lithography"; Fritze et al.; Journal Vacuum. Sci Technology B; Vol. 19, No. 6, pp. 1366-1370; Nov/Dec 2001
	AR	
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Examiner Signature 	Date Considered 09/17/05
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Substitute Disclosure Form (PTO-1449)

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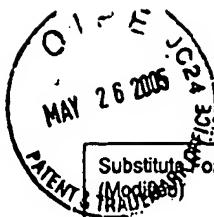
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Other Documents (include Author, Title, Date, and Place of Publication)		
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WD	AH	M. Fritze, et al., "Gratings of regular arrays and trim exposures for ultralarge scale integrated circuit phase-shift lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 19(6):2366-2370, Nov/Dec 2001.
WD	AI	J.A. Hoffnagle, et al., "Liquid immersion deep-ultraviolet interferometric lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 17(6):3306-3309, Nov/Dec 1999.
WD	AJ	Marc D. Levenson, et al., "Exposing the DUV SCAAM - 75 nm Imaging on the Cheap!", <i>Proc. of SPIE: Design, Process Integration, and Characterization for Microelectronics</i> , 4692:288-297, March 2002.
WD	AK	Alex K. Raub, et al., "Deep UV immersion interferometric lithography", <i>Proc. of SPIE: Optical Microlithography XVI</i> , 5040:667-678, Feb. 2003.
WD	AL	Bruce W. Smith, et al., "Water immersion optical lithography at 193 nm", <i>J. Microlith., Microfab., Microsyst.</i> , 3(1):44-51, Jan. 2004.
WD	AM	Akiyoshi Susuki, et al., "Multilevel imaging system realizing $k_1=0.3$ lithography", <i>Proc. of SPIE: Optical Microlithography XII</i> , 3679:396-407, Mar. 1999.
WD	AN	M. Switkes, et al., "Extending optics to 50 nm and beyond with immersion lithography", <i>J. of Vacuum Science &amp; Technology B</i> , 21(6):2794-2799, Nov/Dec 2003.
WD	AO	Brian Tyrrell, et al., "Investigation of the physical and practical limits of dense-only phase shift lithography for circuit feature definition", <i>J. Microlith., Microfab., Microsyst.</i> , 1(3):244-252, Oct. 2002.
WD	AP	Saleem H. Zaidi, et al., "Multiple exposure interferometric lithography", <i>Proc. of SPIE: Optical Microlithography VII</i> , 2197:869-875, Mar. 1994.
WD	AQ	M. Fritze, et al., "Preprint of poster presentation entitled "High-Throughput Hybrid Optical Maskless Lithography: All-Optical 32-nm Node Imaging," Presented at SPIE Microlithography 2005, San Jose, California, USA, March 3, 2005.

Examiner Signature <i>Dorothy L. Davis</i>	Date Considered 09/17/05
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<b>U.S. Patent Documents</b>							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
ND	AA	2005/0073671	04/2005	Borodovsky			
ND	AB	2005/0074698	04/2005	Borodovsky			
ND	AC	2005/0083497	04/2005	Borodovsky			
ND	AD	2005/0085085	04/2005	Borodovsky			
ND	AE	5,759,744	06/1998	Brueck, et al.			
NP	AF	6,042,998	03/2000	Brueck, et al.			
ND	AG	6,233,044	05/2001	Brueck, et al.			
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U.S. Patent Documents							
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ND	AA	5,759,744	June 2, 1998	Brueck, et al.			
ND	AB	5,415,835	May 16, 1995	Brueck, et al.			
ND	AC	5,328,807	July 12, 1994	Tanaka, et al.			
ND	AD	6,553,562	April 22, 2003	Capodieci, et al.			
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ND	AL	EP 0855623	July 29, 1998	EP			
ND	AM	WO 98/32054	July 23, 1998	PCT			
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Other Documents (include Author, Title, Date, and Place of Publication)		
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ND	AQ	Ishibashi, et al., "AFM Lithography Combined with Optical Lithography", <i>IEEE Microprocesses and Nanotechnology Conference 2000</i> , pp. 192-193 (July 2000).
ND	AR	Martin, et al., "Ordered Magnetic Nanostructures: Fabrication and Properties", <i>J. Magnetism and Magnetic Materials</i> , 256(1-3):449-501 (January 2003).
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DW	AA	2003/0091940	05/2003	Nakao	—	—	
DW	AB	5,705,321	01/1998	Brueck, et al.	—	—	
	AC				—	—	
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	AE				—	—	
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							Yes No
DW	AL	0 915 384	05/1999	Europe	—	—	
DW	AM	0 964 305	12/1999	Europe	—	—	
DW	AN	WO2005/036273	04/2005	WIPO	—	—	
	AO				—	—	
	AP				—	—	

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
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Examiner Signature <i>Abdullah</i>	Date Considered <i>09/17/05</i>
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